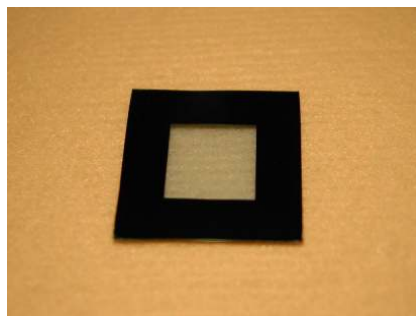


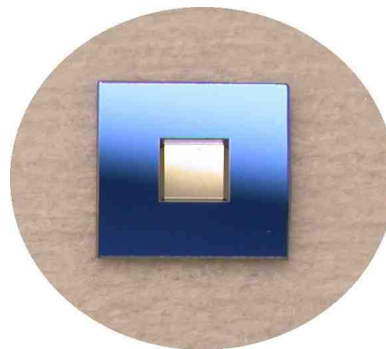


NITRIDE WINDOWS FOR X-RAY, IR & UV SPECTROSCOPY

Norcada manufactures a wide range of high quality silicon nitride windows for the X-ray, IR, and UV spectroscopy research communities. Our standard silicon nitride windows are fabricated on silicon frames with different window and frame sizes to choose from. The silicon nitride is low stress and robust, and is ideally suited for sample mounting in spectroscopy work. Norcada warrants the quality of its silicon nitride windows, and will replace any device deemed unusable due to fabrication defects within 90 days of purchase.



Top view of a NX10500A nitride window



Backside view of a NX5100C nitride window

Standard Nitride Windows

NX Series Nitride Windows on 5x5mm 200µm Thickness Silicon Frame					
Part Number	Window Size	Nitride Thick.	Part Number	Window Size	Nitride Thick.
NX5025A	0.25x0.25mm	50nm	NX5100A	1.0x1.0mm	50nm
NX5025B	0.25x0.25mm	75nm	NX5100B	1.0x1.0mm	75nm
NX5025C	0.25x0.25mm	100nm	NX5100C	1.0x1.0mm	100nm
NX5050A	0.5x0.5mm	50nm	NX5150A	1.5x1.5mm	50nm
NX5050B	0.5x0.5mm	75nm	NX5150B	1.5x1.5mm	75nm
NX5050C	0.5x0.5mm	100nm	NX5150C	1.5x1.5mm	100nm
NX Series Nitride Windows on 7.5x7.5mm 200µm Thickness Silicon Frame					
Part Number	Window Size	Nitride Thick.	Part Number	Window Size	Nitride Thick.
NX7050A	0.5x0.5mm	50nm	NX7150A	1.5x1.5mm	50nm
NX7050C	0.5x0.5mm	100nm	NX7150C	1.5x1.5mm	100nm
NX7100A	1.0x1.0mm	50nm	NX7150D	1.5x1.5mm	200nm
NX7100C	1.0x1.0mm	100nm	NX7150E	1.5x1.5mm	500nm
NX7200D	2.0x2.0mm	200nm	NX7200E	2.0x2.0mm	500nm
NX Series Nitride Windows on 10x10mm 200µm Thickness Silicon Frame					
Part Number	Window Size	Nitride Thick.	Part Number	Window Size	Nitride Thick.
NX10300A	3.0x3.0mm	50nm	NX10500A	5.0x5.0mm	50nm
NX10300C	3.0x3.0mm	100nm	NX10500C	5.0x5.0mm	100nm
NX10300D	3.0x3.0mm	200nm	NX10500D	5.0x5.0mm	200nm
NX10300E	3.0x3.0mm	500nm	NX10500E	5.0x5.0mm	500nm
NX10300F	3.0x3.0mm	1000nm	NX10500F	5.0x5.0mm	1000nm



NITRIDE WINDOWS FOR X-RAY, IR & UV SPECTROSCOPY

● Silicon Nitride Film Properties

Deposition method: LPCVD (Low Pressure Chemical Vapor Deposition)

Thickness variation: $\pm 7\%$

Film stress level: < 250 MPa (tensile)

Refractive index: 2.20 ± 0.05

● Contact information



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